



# 8/A  
5/20/03 Hayes  
DOCKET NO: VSEA 005-99

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Charles M. McKenna et al.  
Serial No: 09/602,059  
Confirmation No: 9493  
Filed: June 23, 2000  
For: ION IMPLANTER HAVING TWO-STAGE DECELERATION  
BEAMLINE  
Examiner: Mary A. El-Shammaa  
Art Unit: 2881

**CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)**

The undersigned hereby certifies that this document is being placed in the United States mail with 1 first-class postage attached, addressed to Commissioner for Patents, Washington, D.C. 20231, on the 6 day of May, 2003.

Cheryl A. Purcell  
Cheryl Purcell

Commissioner for Patents  
Washington, D.C. 20231

Sir:

**AMENDMENT**

In response to the Office Action mailed November 6, 2002, please amend the above-identified application as follows.

**In the Claims**

Please amend claims 1, 15, 30, 37, 45 and 52 to read as follows. Marked-up copies of the amended claims, with changes indicated by bracketing and underlining, are enclosed.

1. (As Amended) An ion implanter comprising:

A1

- an ion source for generating an ion beam at a first voltage  $V_0$ ;
- an analyzer for separating unwanted components from said ion beam;
- a beam transport device for transporting said ion beam through said analyzer at a first transport energy;